

APPLICATION DATA SHEET

APPLICATION INFORMATION

Application Type::

Regular `

Subject Matter::

Utility

Title::

SUBSTRATE FOR PHOTOMASK, PHOTOMASK

BLANK AND PHOTOMASK

Attorney Docket Number::

Q80708

Request for Early Publication?::

No

Request for Non-Publication?::

No

Small Entity?::

No

APPLICANT INFORMATION

Applicant Authority Type::

Inventor

Primary Citizenship Country::

JAPAN

Status::

Full Capacity

Given Name::

Ryu

Family Name::

OHTAGURO

City of Residence::

Kumamoto

Country of Residence::

JAPAN

Street of mailing address::

338-2, Kamimachi, Ozu-machi,

Kikuchi-gun,

City of mailing address::

Kumamoto

Country of mailing address::

JAPAN

Applicant Authority Type::

Inventor

Status::

Full Capacity

Given Name::

Koichi

Family Name::

HASHIGUCHI

City of Residence::

Kumamoto

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Country of Residence::

JAPAN

Street of mailing address::

4-4-142, Omine, Kumamoto-shi,

City of mailing address::

Kumamoto

Country of mailing address::

JAPAN

CORRESPONDENCE INFORMATION

Correspondence Customer Number::

23373

Phone number::

(202) 293-7060

Fax Number:

(202) 293-7860

E-Mail address::

sughrue@sughrue.com

REPRESENTATIVE INFORMATION

Representative Customer Number::

23373

FOREIGN PRIORITY INFORMATION

Country::

Application number::

Filing Date::

Priority Claimed::

JAPAŃ

2003-084992

03/26/03

Yes

JAPAN

2004-073763

03/16/04

Yes

ASSIGNEE INFORMATION

Assignee name::

HOYA CORPORATION

Street of mailing address::

7-5, Naka-Ochiai 2-chome,

Shinjuku-ku,

City of mailing address::

Tokyo,

Country of mailing address::

JAPAN